

GS17 Semiconductor manufacturing and metrology

GS17-01 Enhancing Dataset Variability in Semiconductor Manufacturing through Domain Adaptation and Advanced Simulation Techniques
Chong-Han Hsu, Eugene Su, Bo-En Tsai and Chao-Ching Ho
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GS17-03 New DUV Wavelength - Scanning Scatterometry for Sub-Micron High-Aspect-Ratio OCD Metrology
Fu-Sheng Yang, Min-Ru Wu, Yen-Hung Hung, Yuan-Ci Lin, Bo-Chen Kuo and Liang-Chia Chen

GS17-04 Optimizing Fourier Hyperspectral Scatterometry with Global Sensitivity Analysis for Semiconductor OCD Metrology
Yen-Hung Hung, Min-Ru Wu, Fu-Sheng Yang, Bo-Chen Kuo, Yuan-Ci Lin, Surajit Das and Liang-Chia Chen
National Taiwan University

GS17-05 Basic study of plasma dicing for SiC wafer using high-pressure plasma
Shunto Iden, Yuken Matsumura, Jumpei Yamada, Daisetsu Toh, Kazuto Yamauchi and Yasuhisa Sano
Osaka university

GS17-06 Dimension reduction of electromagnetic field on the top surface of 3D through silicon via array by using singular value decomposition
Song-En Chen, Chih-Chung Wang and Jia-Han Li
National Taiwan University